

last name

first name

title

company / institute / university

street

zip/city

e-mail

Deutsche Gesellschaft für Galvano-
und Oberflächentechnik e. V.

P. O. Box 10 10 63

D-40710 Hilden

Germany

phone

fax

REGISTRATION

Please fill in the form attached and send it to:

Barbara Herrmann
Deutsche Gesellschaft für Galvano- und Oberflächentechnik e.V.
P.O. Box 10 10 63 · D-40724 Hilden

Phone: +49 2103 25 56 50
Fax: +49 2103 25 56 56
e-mail: b.herrmann@zvo.org

CONFERENCE FEE

The conference fee is 390 €. Students: 50 € (student-ID required).

It includes beverages, lunch on both days and dinner on Sept. 23rd, 2009.

If you wish to participate at the Oberflächentage as well, please contact b.herrmann@zvo.org.

After your registration you will receive an invoice which is to be paid within 5 days. In case of a written cancellation until Aug. 23rd, 2009 the conference fee will be refunded (cancellation fee is 15 €).

In case of a cancellation after Aug. 23rd the conference fee will NOT be reimbursed. However, the registration of a substitute is possible.

ACCOMODATION

The symposium takes place at the

Maritim Hotel & Congress Centrum Bremen · Germany
Hollerallee 99 · 28215 Bremen
Tel.: +49 421 3789-610
Fax: +49 421 3789-684

For reservation please contact and remark "DGO"
<http://www.maritim.de/typo3/english/hotels/hotels/hotel-bremen.html>
or contact the tourist information in Bremen:
Schmidling@bremen-tourism.de

Forms are available at the website www.dgo-online.de

DIRECTIONS FROM AIRPORT BREMEN TO THE MARITIM HOTEL & CONGRESS CENTRUM BREMEN

You can take a taxi or tram Nr. 6 directly from the airport. Get off at the central station. Walk across the station building, then straight on across the Bürgerweide and then past the AWD Dome. You can see the hotel on the left. It takes 5-7 minutes to get there.

DGO



Program

EUROINTERFINISH 2009



BREMEN, GERMANY

23 – 24 SEPTEMBER 2009

In Cooperation with

ZVO
Zentralverband
Oberflächentechnik

OBERFLÄCHENTAGE 2009

SCOPE

The EUROINTERFINISH 2009 will continue the tradition of the previous, successful symposia. Following the general tendency in science, equal emphasis is put on plating technology and applied surface finishing. The scope of this symposium ranges from fundamental research over applied research and development up to industrial applications.

The symposium will be especially focused on

Pulse Plating and Other Electrochemical Techniques

LANGUAGE

The official language of the conference is English.

PUBLICATIONS

Full research papers will be published in the Journal for Electrochemistry and Plating Technology.

All papers will be peer reviewed utilizing the normal submission process

ADVISORY BOARD

W. Paatsch, Germany (Chair)

P. Cavallotti, Italy

W. Hansal, Austria

A. Möbius, Germany

C. Müller, Spain

K. Pinkwart, Germany

J.-C. Puipe, Switzerland

P. Schmutz, Switzerland

D. Thery, France

H.T. Yum, South Korea

A. Zielonka, Germany

PULSE PLATING AND OTHER ELECTROCHEMICAL TECHNIQUES

23.09.2009

08:30	Registration and Welcome Coffee	
08:55	Welcome	H. T. Yum, President IUSF
09:00	Plenary Lecture: Pulse Plating for Automotive Industry	W.E.G. Hansal, S. Hansal, M. Halmdienst, G. Sandulache; Austria
	Pulse Plating	Chair: W. Paatsch
09:30	Pulsed Electrodeposition of Metal Matrix Composites with Diamond Particles	P. L. Cavallotti, P. Cojocar, L. Magagnin; Italy
10:00	Pulse Plating on Nickel based Composite Coatings	A. Zoukis - Karathanasis, S. Spanou, G. Gyftou, E.A. Pavlatou, N. Spyrellis; Greece
10:30	Pulse Plating of Silver and Silver Alloys	W.E.G. Hansal, S. Hansal, G. Sandulache, V. Grman; Austria
11:00	<i>Coffee Break</i>	
	Pulse Plating	Chair: W. E. G. Hansal
11:30	Electroless Plating of Highly Corrosion-resistant Ni-W Alloy on Diffusers and Shower Heads	H. T. Yum; South Korea
12:00	Pulsed Electrodeposition of Metals from Ionic Liquids	A. Ispas, A. Bund; Germany
12:30	Influence of Ultrasound on Filling of Grooves during Ni Electrodeposition	N. Gunnarsson, P. Leisner, J. Hald, L. Hultman; Sweden
13:00	The Use of Ultrasound in the Deposition of Metals - An Enabling Technology for Low Energy, Sustainable Plating?	A. Cobley, T. Mason; United Kingdom
13:30	<i>Lunch Break</i>	
	Electrodeposition	Chair: A. Zielonka
14:30	Electrodeposition from Ionic Liquids	A. Möbius, C. Werner; Germany
15:00	Electropolishing and Pickling of Stainless Steel as a Precursor to Silanisation for New Finishes with Enhanced Properties	L. A. Jones, E. Garcia, I. Etxebarria, J. A. Diez Silanes; Spain
15:30	Effects of Adsorption on the Electrodeposition of Silver from Cyanide Solutions	J. P. G. Farr; United Kingdom
16:00	The Effect of Both Different Additives and Pulse Current on the Codeposition of SiC Nano-Particles in Nickel Matrix Deposits	M. Lekka, V. Conci, A. Lanzutti, C. Zanella, L. Fedrizzi, P. L. Bonora; Italy
16:30	<i>End of daily programme</i>	
17:00	Opening ceremony ZVO Oberflächentage 2009 Maritim-Hotel Bremen	
19:15	Transfer to the Get Together Party (departure Maritim-Hotel)	
19:30	Get Together Party Friesenhof Bremen	

24.09.2009

08:45	Plenary Lecture Oberflächentage 2009	
	Nanostructuring	Chair: Th. Lampke
10:00	Electrochemical Planarization of Bio-Implantable Ti Alloys	L. Neelakantan, S. Drenser, G. Eggele, A.W. Hassel; Germany
10:30	Electrochemical Processes for the Production of Nanopatterned and Functional Surfaces on Titanium	M. Ürgen, Turkey
11:00	In-situ Microtribology with High Local Resolution	W. P. Weinhold; Germany
11:30	<i>Coffee Break</i>	
	Analysis	Chair: J. P. G. Farr
12:00	XRF Thickness Measurement of Thin Au and Pd Layers on Printed Circuit Boards	S. Dill, V. Rößiger; Germany
12:30	A New Simulation Technique of Electrodeposition Processes	W. Paatsch, G. Mollath; Germany
13:00	Design and Optimization of CP Systems for Marine Applications	L. Bortels, J. Parlongue; Belgium
13:30	<i>Lunch Break</i>	
	New Systems	Chair: P. L. Cavallotti
14:30	Water-based Protective Silane Coatings Doped with Corrosion Inhibitors	S. Darwich, Th. Lampke, B. Wielage, S. Steinhäuser; Germany
15:00	Recent Surface Finishing Technology Related to the Environmental Protection	M. Kume; Japan
15:30	Final remarks and Farewell	

